Notice of Allowability	Application No.	Applicant(s)
	10/646,709	OHNISHI, SADAYUKI
	Examiner	Art Unit
	Phat X. Cao	2814
The MAILING DATE of this communication appeall claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this apport or other appropriate communication GHTS. This application is subject to	olication. If not included will be mailed in due course. THIS
1. This communication is responsive to <u>11/9/05</u> .		
2. The allowed claim(s) is/are 1-13,25 and 26.		
 Acknowledgment is made of a claim for foreign priority unally All b) Some* c) None of the: Certified copies of the priority documents have Certified copies of the priority documents have Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). 	e been received. e been received in Application No	
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		
4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.		
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.		
(a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached		
1) hereto or 2) to Paper No./Mail Date		
(b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date		
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on the drawing the header according to 37 CFR 1.121(ngs in the front (not the back) of d).
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.		
Attachment(s) 1. Notice of References Cited (PTO-892)	5 □ Notice of Informal F	Patent Application (PTO-152)
2. Notice of References Cited (F10-692)	6. ☐ Interview Summary	
	Paper No./Mail Da	te
3. Information Disclosure Statements (PTO-1449 or PTO/SB/C Paper No./Mail Date	08), 7. ⊠ Examiner's Amendr	ment/Comment
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. Examiner's Statement	ent of Reasons for Allowance
or brorogram material	9. Other	
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EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

IN THE CLAIM:

Claim 1, line 1, insert ":" right after "order"

2. The following is an examiner's statement of reasons for allowance: the prior art of record fails to disclose all the limitations recited in the base claims. Specifically, the prior art of record fails to disclose the combination of a semiconductor device structure comprising: first and second low dielectric constant films, a silicon dioxide layer, first and second copper diffusion barrier layers, and an adhesive film constituted essentially by a silicon-based compound having an aromatic ring in a molecule of the silicon-based compound having a specific dielectric constant of 2.5 to 2.6 as recited in claim 1.

The prior art of record also fails to disclose a second adhesive film constituted essentially by a silicon-based compound having an aromatic ring in a molecule of the silicon-based compound having a specific dielectric constant of 2.5 to 2.6 being formed between a SiCN layer and the low dielectric constant film (claim 25) or between a silicon dioxide layer and the low dielectric constant film (claim 26).

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Phat X. Cao whose telephone number is 571-272-1703. The examiner can normally be reached on M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on 571-272-1705. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

PC

November 22, 2005

PHAT X. CAO
PRIMARY EXAMINER

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